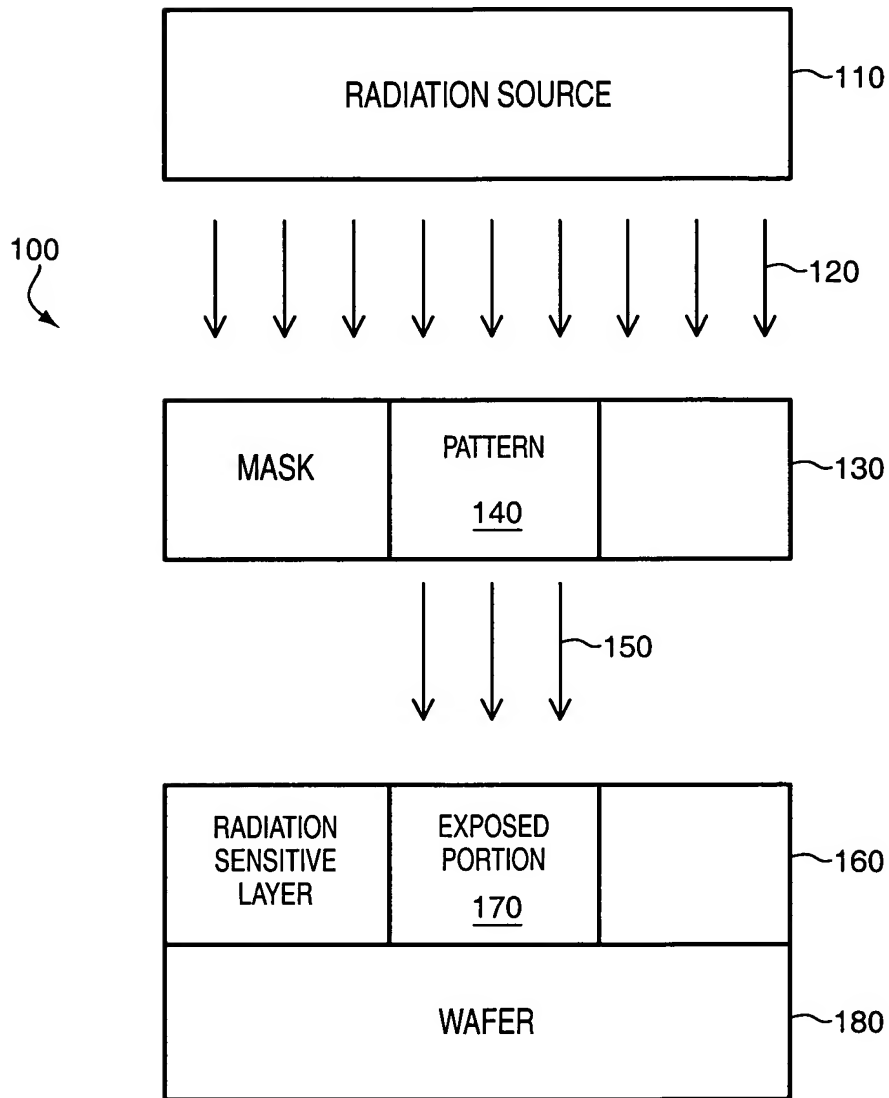
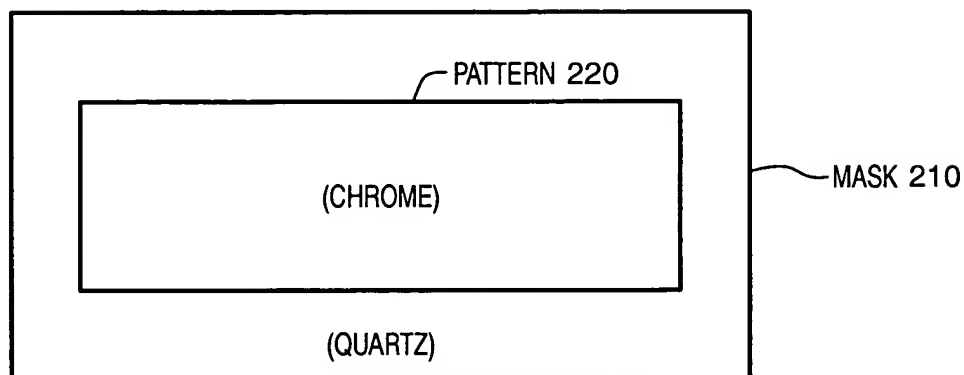


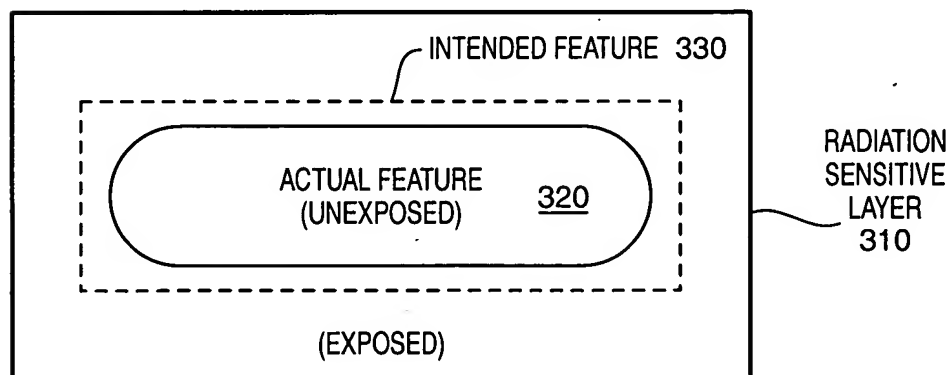


**FIG. 1**

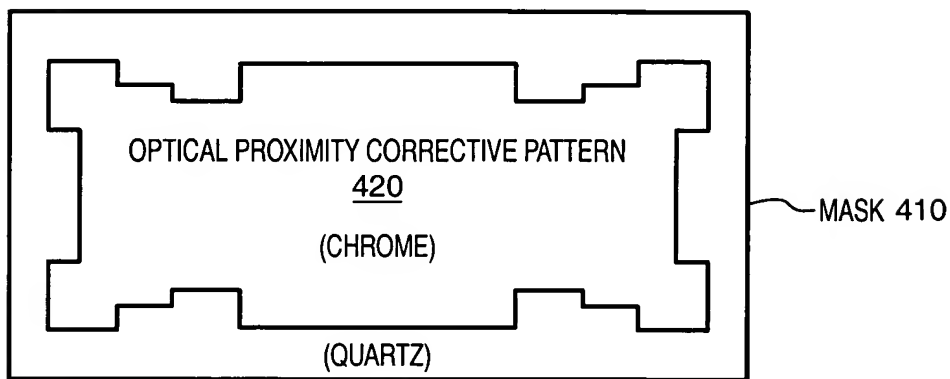




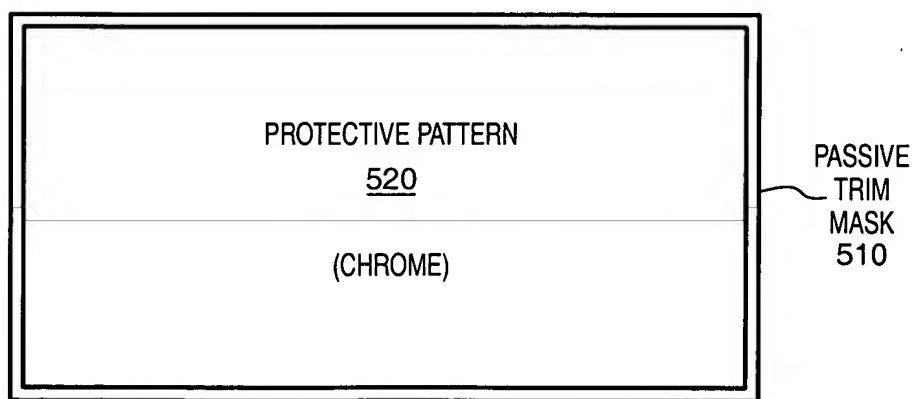
**FIG. 2**



**FIG. 3**



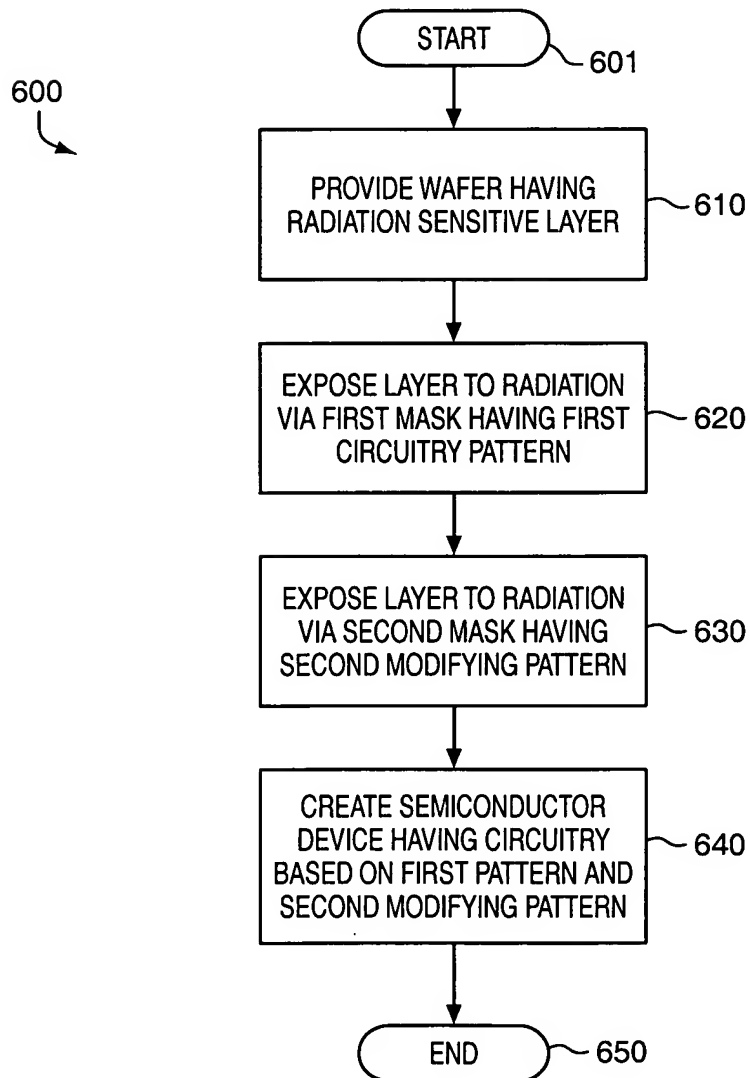
**FIG. 4**



**FIG. 5**



**FIG. 6**

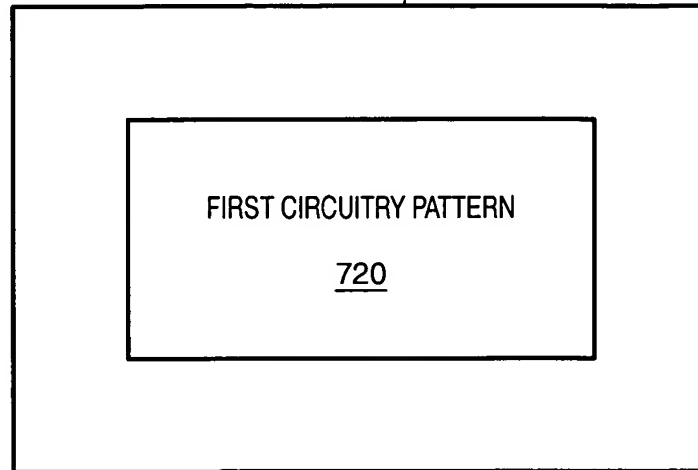




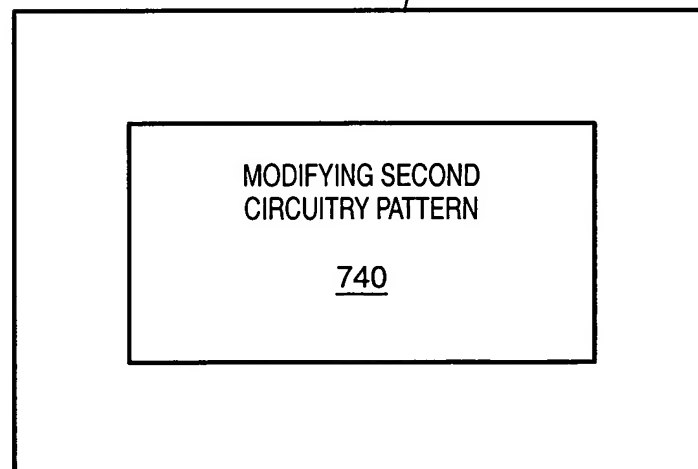
SET OF  
MASKS  
700



FIRST MASK 710



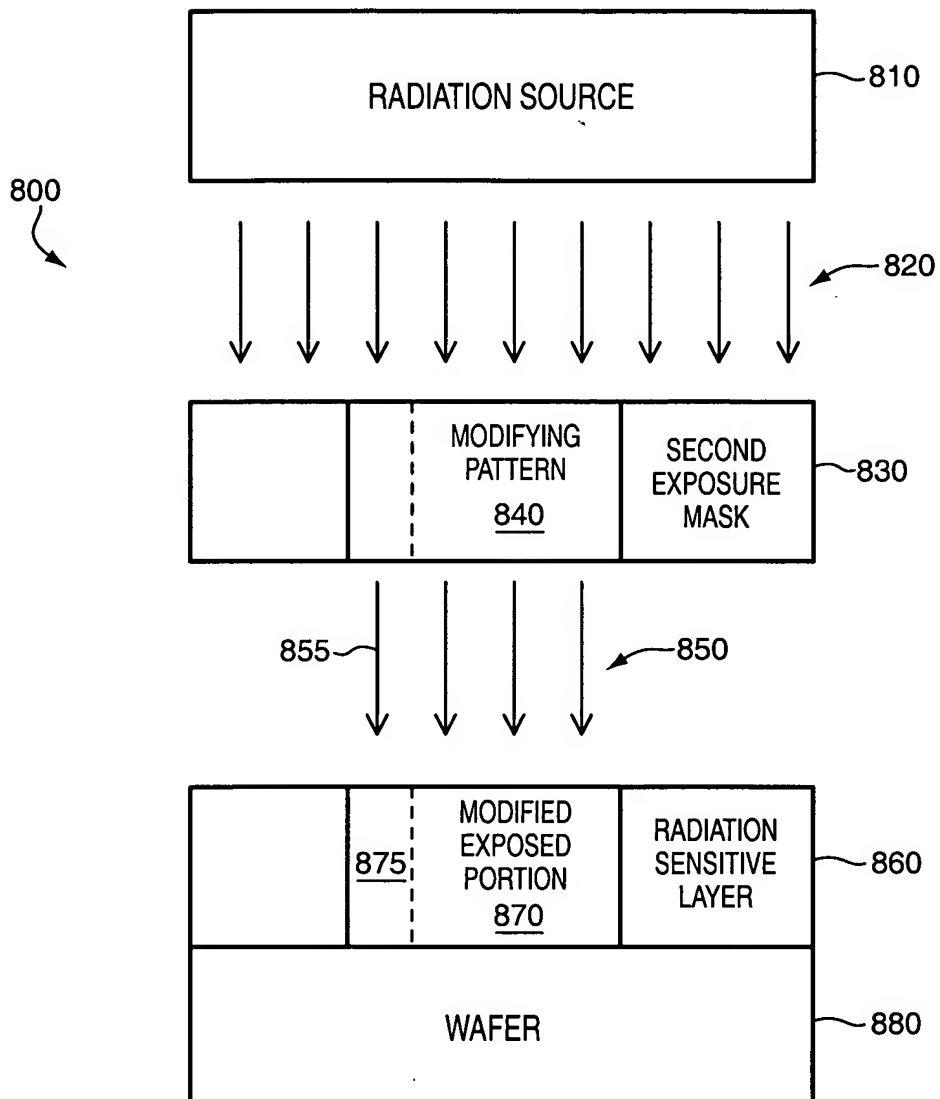
SECOND MASK 730



**FIG. 7**

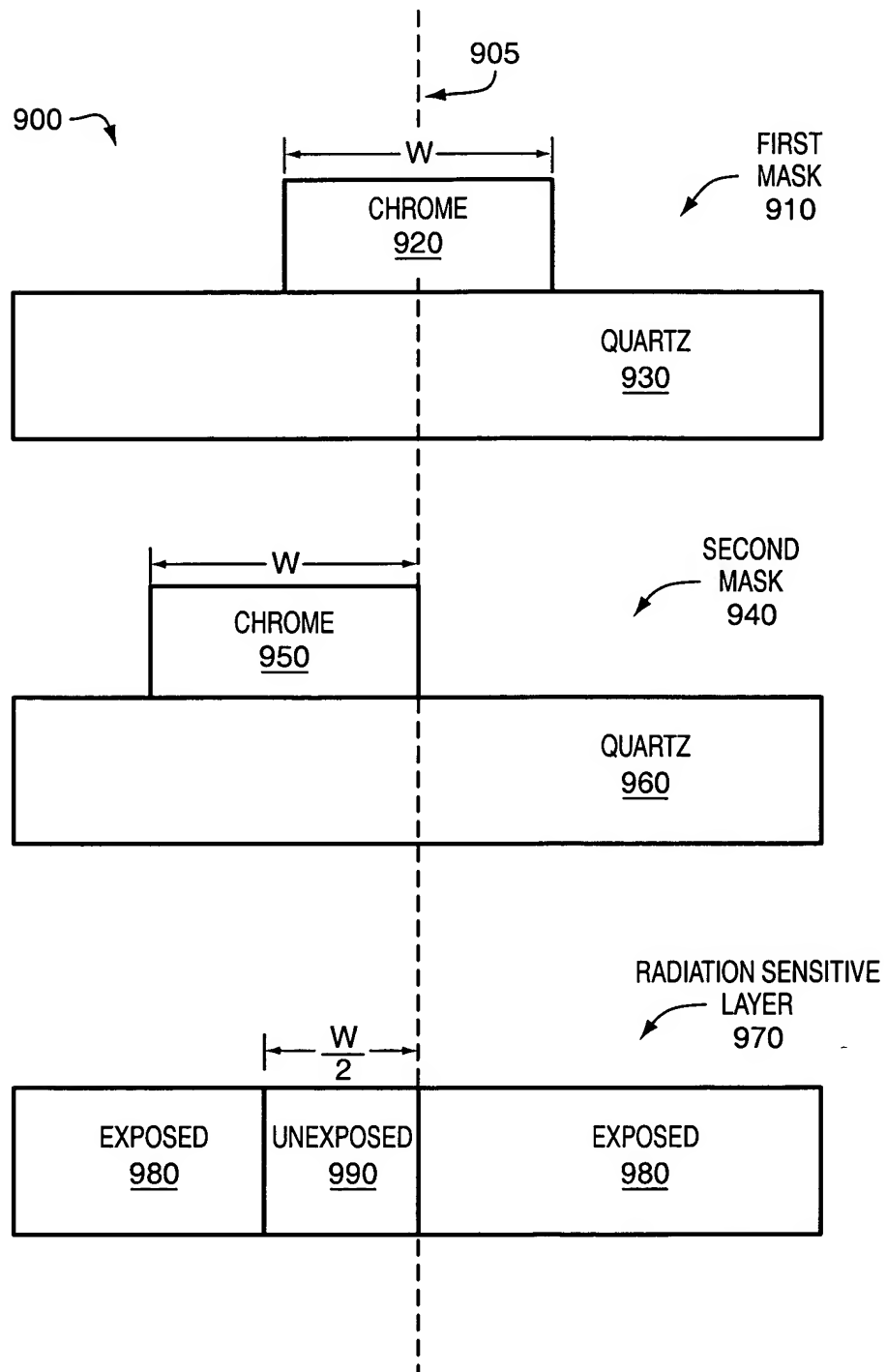


**FIG. 8**

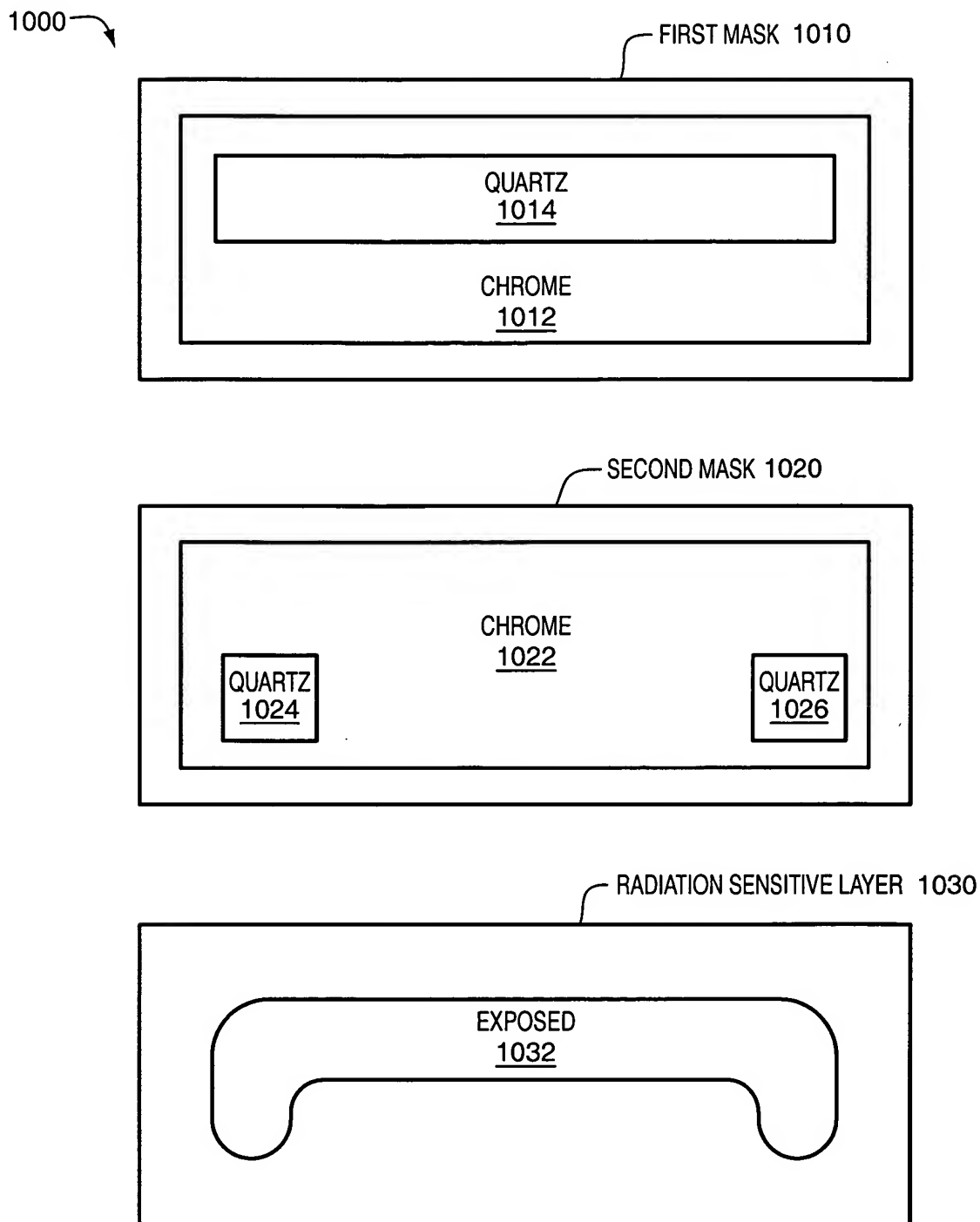




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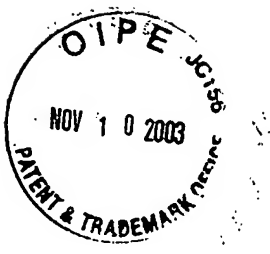


**FIG. 9**

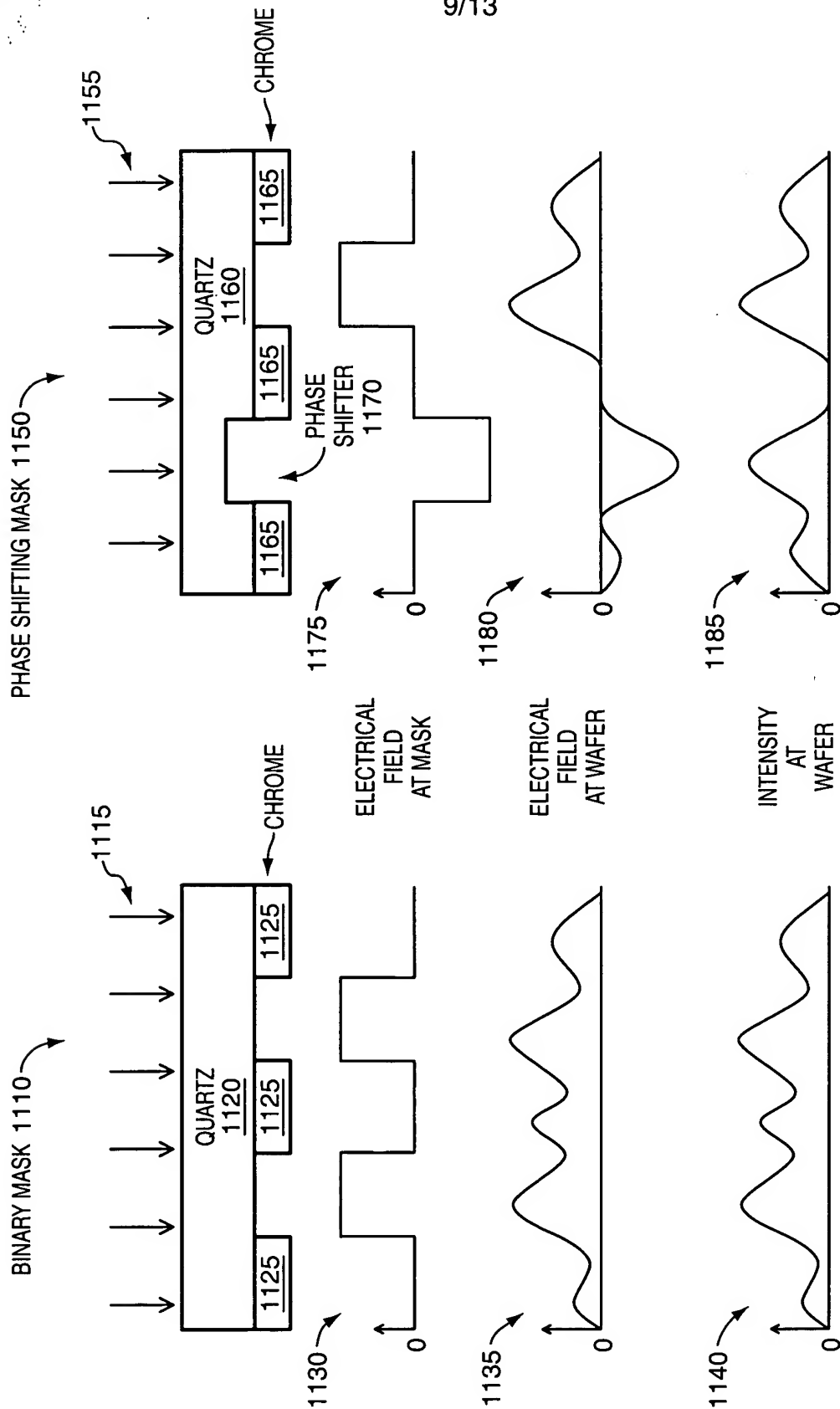


**FIG. 10**

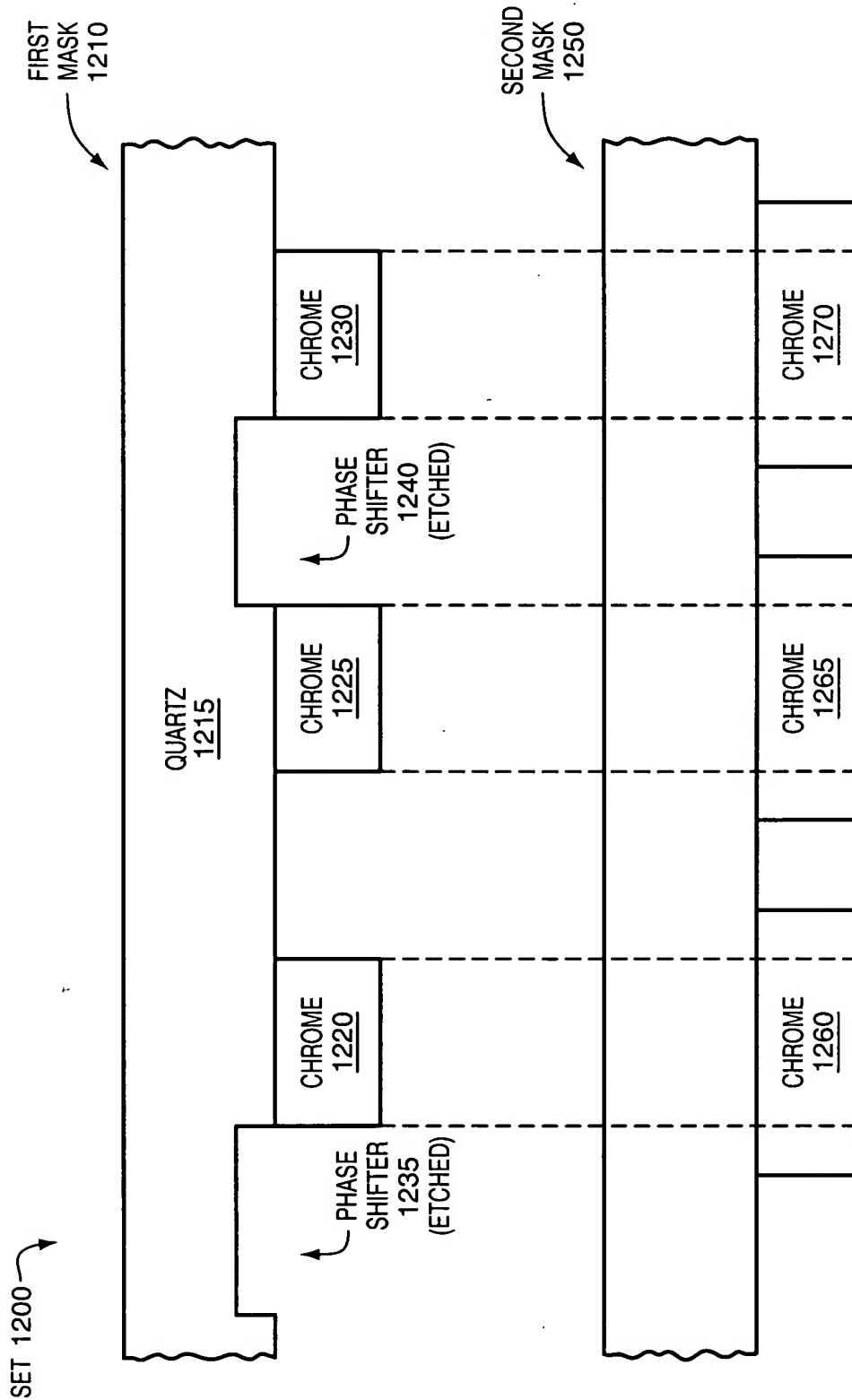




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**FIG. 11**

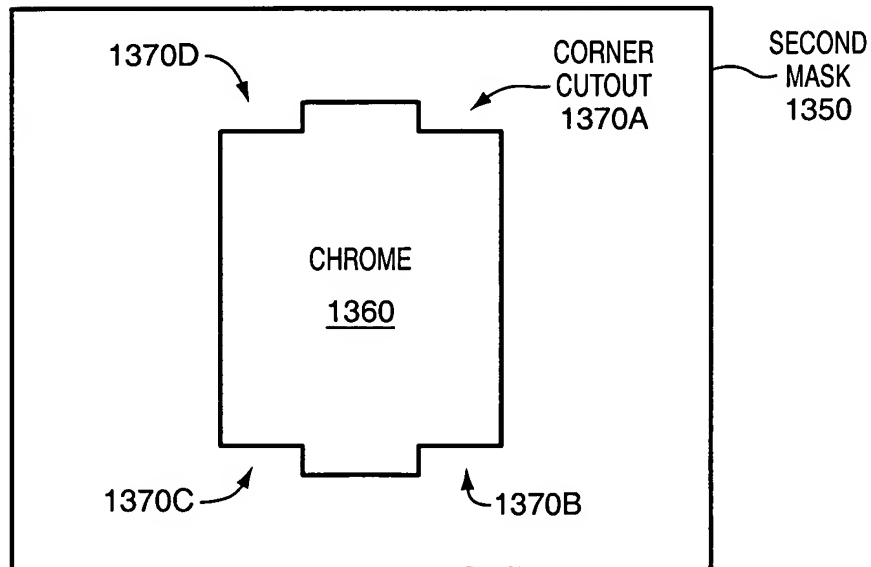
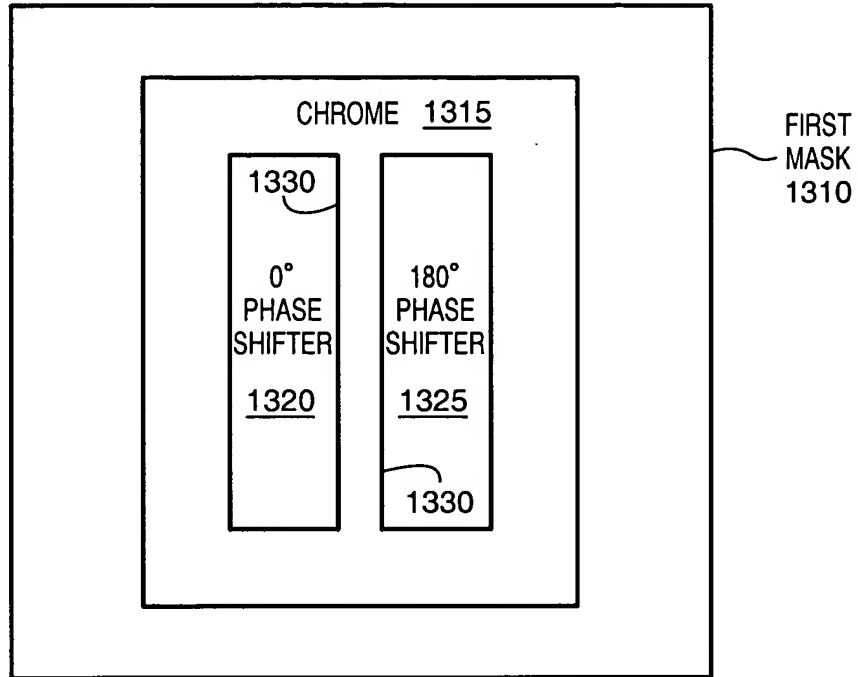


**FIG. 12**



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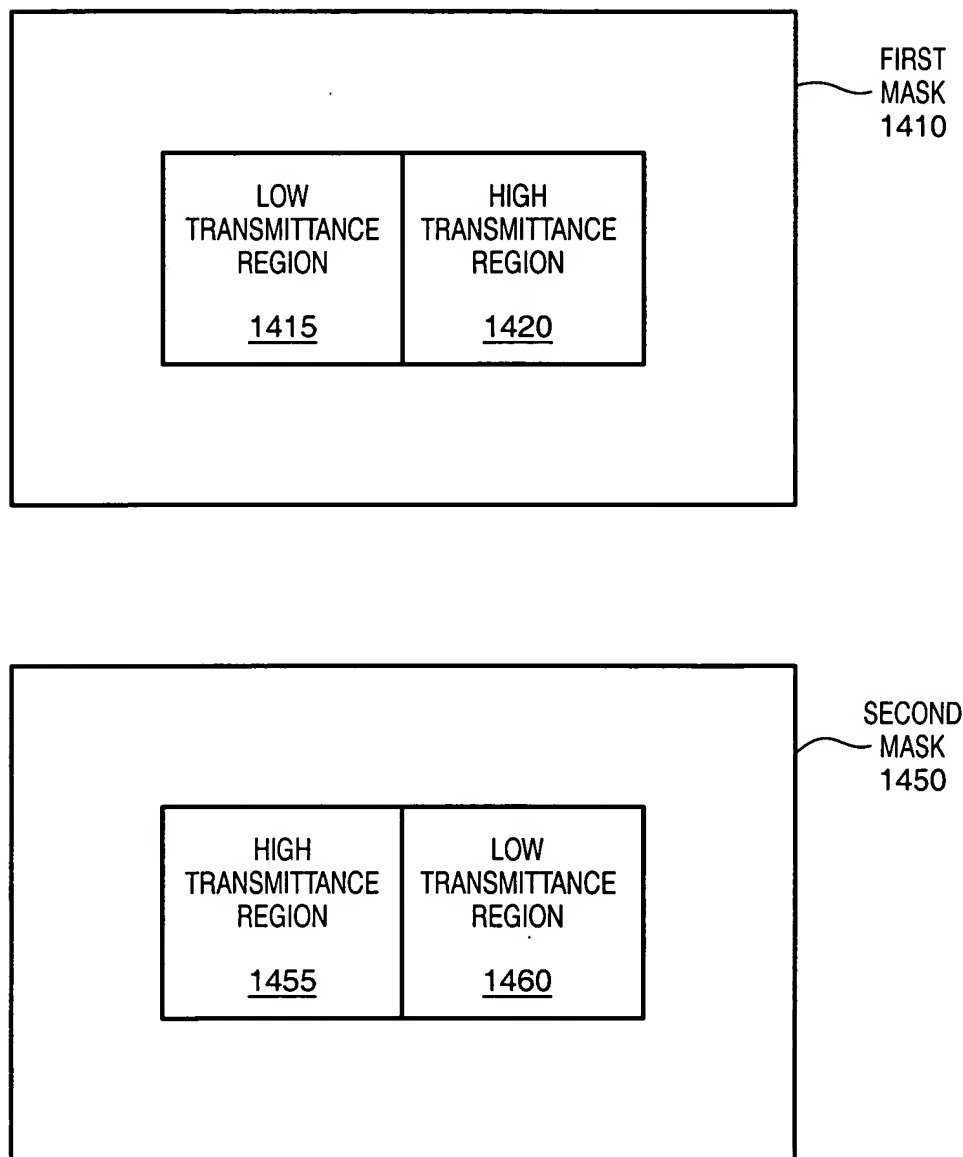
SET  
1300



**FIG. 13**



SET  
1400

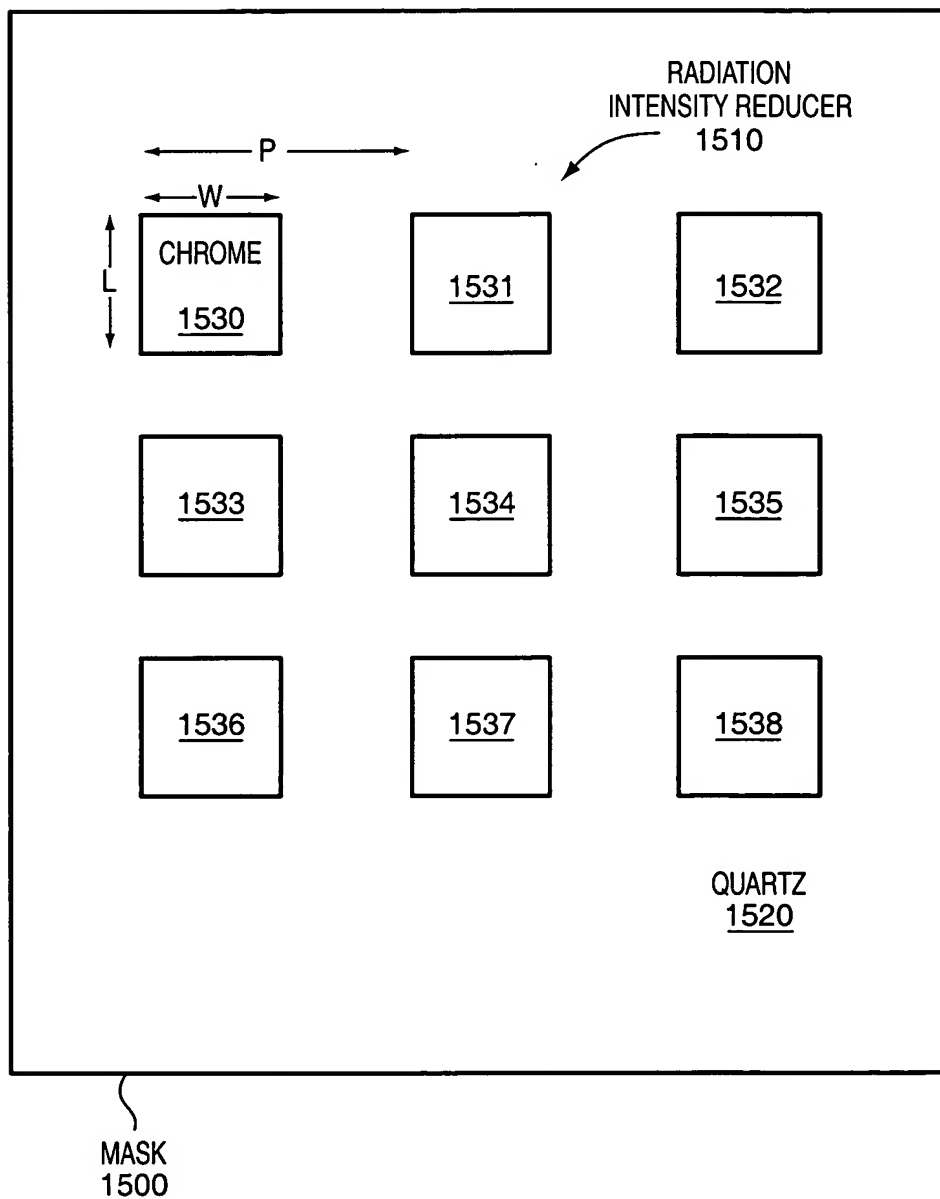


**FIG. 14**



Title: "An Active Secondary Exposure Mask To Manufacture Integrated Circuits"  
Inventors: Fred Chen et al. Application No.: 10/040,772 Attorney Docket No.: 42P11369  
Blakely, Sokoloff, Taylor & Zafman 303-740-1980

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**FIG. 15**